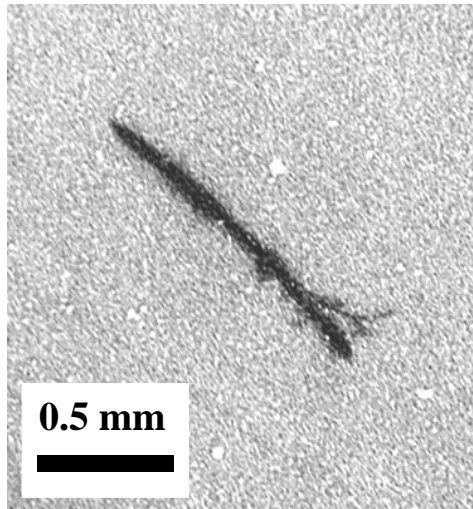


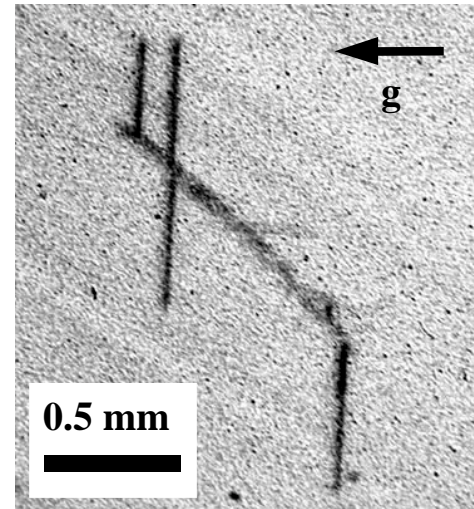


Double Crystal X-Ray Topography: 10^{12} cm^{-2} Si Ion Implant After Anneal

Ion implanted region:



Before Anneal



After Anneal

Misfit dislocation nucleation from surface scratch in implanted region.
Misfit dislocations nucleate and glide in implanted region!

P. Feichtinger, H. Fukuto, R. Sandhu, B. Poust, M.S. Goorsky, D. Oster, S. Rickborn, and J. Moreland, accepted for publication in "Si Front-End Processing- Physics and Technology of Dopant-Defect Interactions II", Materials Research Society.